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n 1449 (Modified)

Atty Docket No. NOVLP030/NVLS-000497 Application No.: 10/016,017

Information Disclosure
Statement By Applicant

Applicant: Gopinath et al.

(Use Several Sheets if Necessary)

Filing Date
December 12, 2001

Group 2812 2813

**U.S. Patent Documents** 

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Foreign Patent or Published Foreign Patent Application

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## Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication						
Se	A	Costantini et al., "Supercritical Fluid Delivery and Recovery System for Semiconductor Wafer Processing", Pub. No.: US 2001/0050096 A1, Pub. Date: Dec. 13, 2001, Appl. No.: 09/837,507, Filed: April 18, 2001, pages 1-15						
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Form 1449 (Modified)  Information Disclosure Statement By Applicant				Atty Docket No.  NOVLP030/NVLS-000497  Application No.:  10/016,017 E  Copinath et al.  Filing Date  Application No.:  Group							
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